

1 Supplementary information

2 of

3 **Electric field-driven one-step formation of vertical p–n junction TiO₂**
4 **nanotubes exhibiting strong photocatalytic hydrogen production**

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6 *Moonsu Kim*^{†,a}, *Jaewon Lee*^{†,b}, *Minyeong Je*^{†,c}, *Bumgi Heo*^a, *Hyeonseok Yoo*^d, *Heechae Choi*^{c,*},

7 *Jinsub Choi*^{a,*}, and *Kiyoung Lee*^{b,e,*}

8
9 a: Department of Chemistry and Chemical Engineering, Inha University,

10 22212 Incheon, Republic of Korea

11 b: Department of Advanced Science and Technology Convergence, Kyungpook National University,

12 37224 Sangju, Gyeongsangbuk-do, Republic of Korea

13 c: Institute of Inorganic Chemistry, University of Cologne

14 50939 Cologne, Germany

15 d: Steel Solution Research Lab., POSCO

16 21985 Incheon, Republic of Korea

17 e: School of Nano & Materials Science and Engineering, Kyungpook National University,

18 37224 Sangju, Gyeongsangbuk-do, Republic of Korea

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20 †: The authors are equally contributed.

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22 *Corresponding authors.

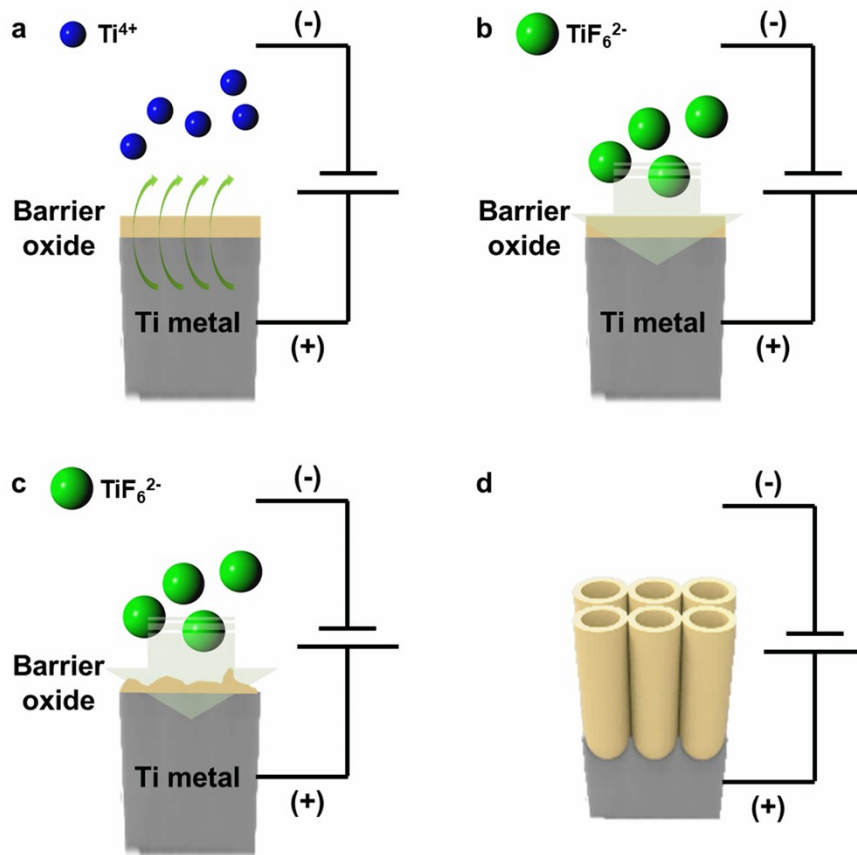
23 E-mail: h.choi@uni-koeln.de (Heechae Choi), jinsub@inha.ac.kr (Jinsub Choi), kiyoung@knu.ac.kr

24 (Kiyoung Lee)

1 **Supplementary information note**

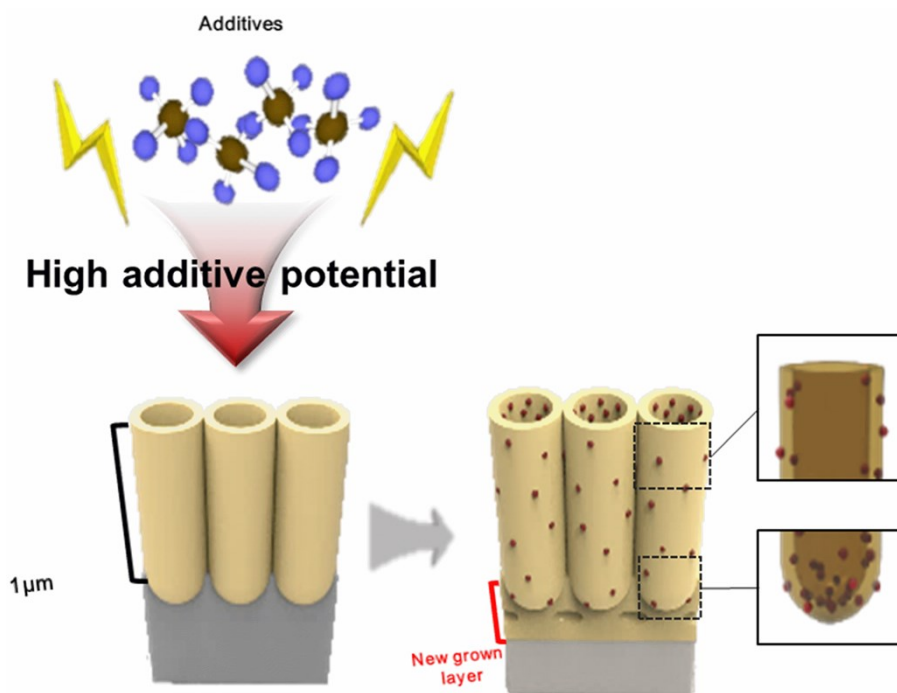
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3 In Supplementary information Scheme 1, the role of fluoride ion in the preparation of the TiO₂
4 nanotube array is comprehensively described. First, the applied potential between the working and
5 counter electrodes formed dissolved metal ions and a barrier oxide layer on the substrate. Generally,
6 the thickness of the oxide layer is proportional to the applied voltage, which is approximately
7 1.4 nm V⁻¹. Second, dissolved metal ions reacted with fluoride ion, thereby forming TiF₆²⁻. They
8 exhibited corrosion properties, such that the formed metal fluoride anions etched the surface of the
9 barrier oxide layer, forming etched pits. Naked metal pits, resulting from the etching made by metal
10 fluoride anions, were deposited into the barrier oxide layer, and this procedure was repeated during
11 the application of the electric field. As a result, the anodic metal oxide structure grew on the substrate;
12 thus, an anodic TiO₂ nanotube array was obtained ¹. For the experimental conditions, 20 V of applied
13 voltage at room temperature for 4 h was used as electric field. With regard to the TiO₂ nanotube array,
14 the nanostructure film, which was formed by the direct growth anodization without binding materials,
15 was able to provide a catalyst with a physically and chemically extensive stable supporting structure,
16 electron-hole pathway, and high surface area. Thereafter, high additive potential was conducted with
17 the dopant-containing electrolyte. It is one of the methods of forcibly intercalating dopants into the
18 TiO₂ nanotube array. After conducting high additive potential, the doped TiO₂ nanotube array was
19 obtained, with an additional grown barrier layer under the array because additional voltage was applied
20 after anodization, such that the barrier oxide layer was additionally coated again, similar to that shown
21 in Supplementary information Schemes 1 and 2.

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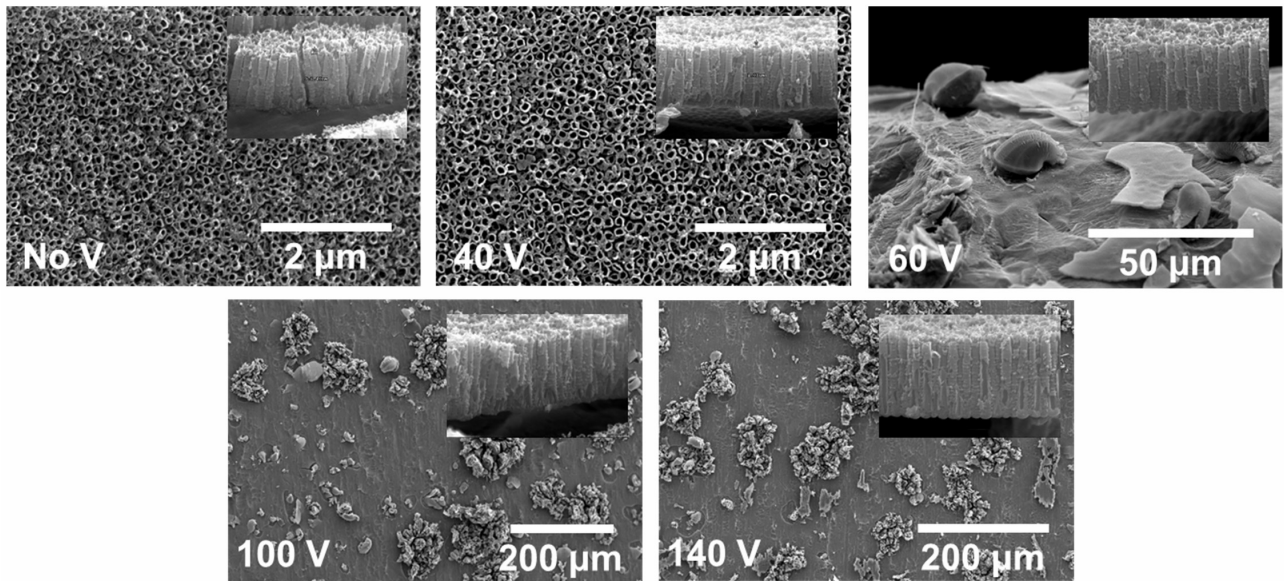


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2 **Supplementary information Scheme 1.** General mechanism describing anodization process.

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5 **Supplementary information Scheme 2.** Additive doping with high additive potential.



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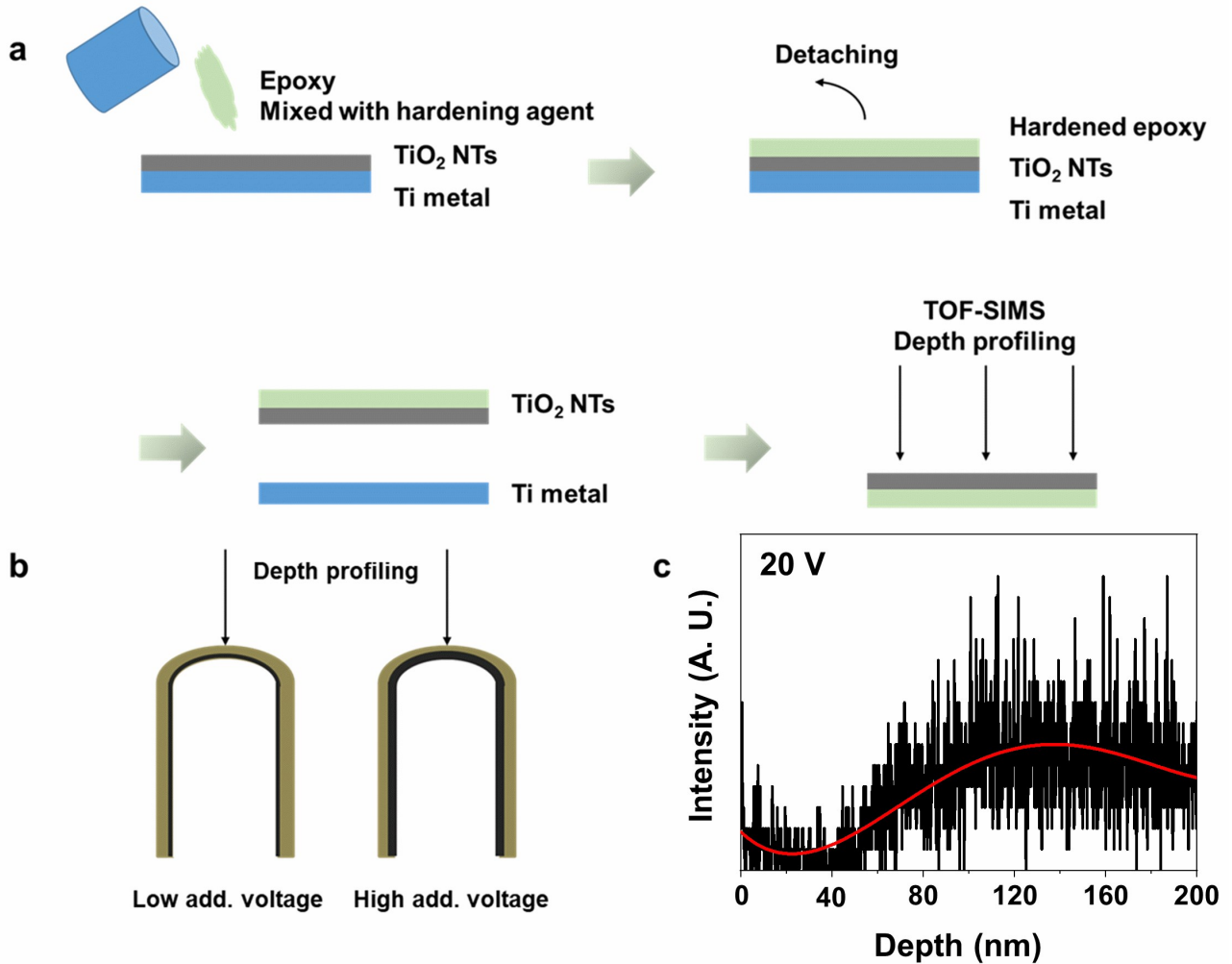
2 **Supplementary information Figure 1.** SEM images of Pd-doped TiO₂ nanotube array at the various applied high
 3 additional voltage levels. Insets exhibit each cross-sectional view.

4

5 In Figure S1, small pits manifested on the surface. This phenomenon is referred to as the rapid
 6 breakdown anodization caused by chloride ions because the etching properties of chloride are stronger
 7 than those of fluoride, such that the products of rapid breakdown anodization are usually nanotube
 8 bundle powders^{2,3}. Notably, however, the TiO₂ nanotube bundle did not manifest after the coating of
 9 the nanotube array because the previously prepared TiO₂ nanotube array probably protected the Ti
 10 substrate. Therefore, despite the chloride ion and high applied voltage, the TiO₂ nanotube array had
 11 been maintained even after a high additional voltage was applied. Well-taken cross-sectional views
 12 were sufficient evidence in determining that the TiO₂ nanotube array was maintained.

1 TOF-SIMS was carried out to detect the depth of the Pd-doped region. Therefore, initially, the
2 TiO₂ nanotube array had to be detached from the substrate so that the epoxy polymer was allowed to
3 be employed as a detacher agent. The detachment of the TiO₂ nanotube array is described below in
4 detail in Figure S2⁴.

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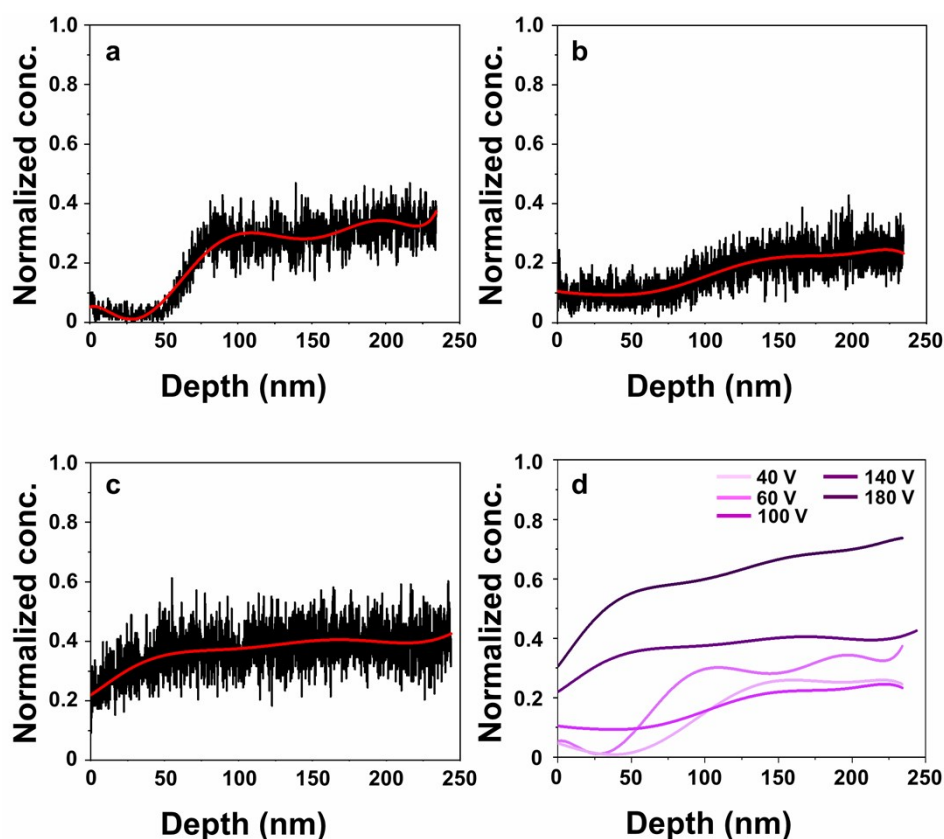
7 **Supplementary information Figure 2.** (a), (b) Procedure of detaching the TiO₂ nanotube array from the substrate. (c)

8 Mass spectrum of the Pd-doped TiO₂ nanotube array with the applied electric field of 20 V.

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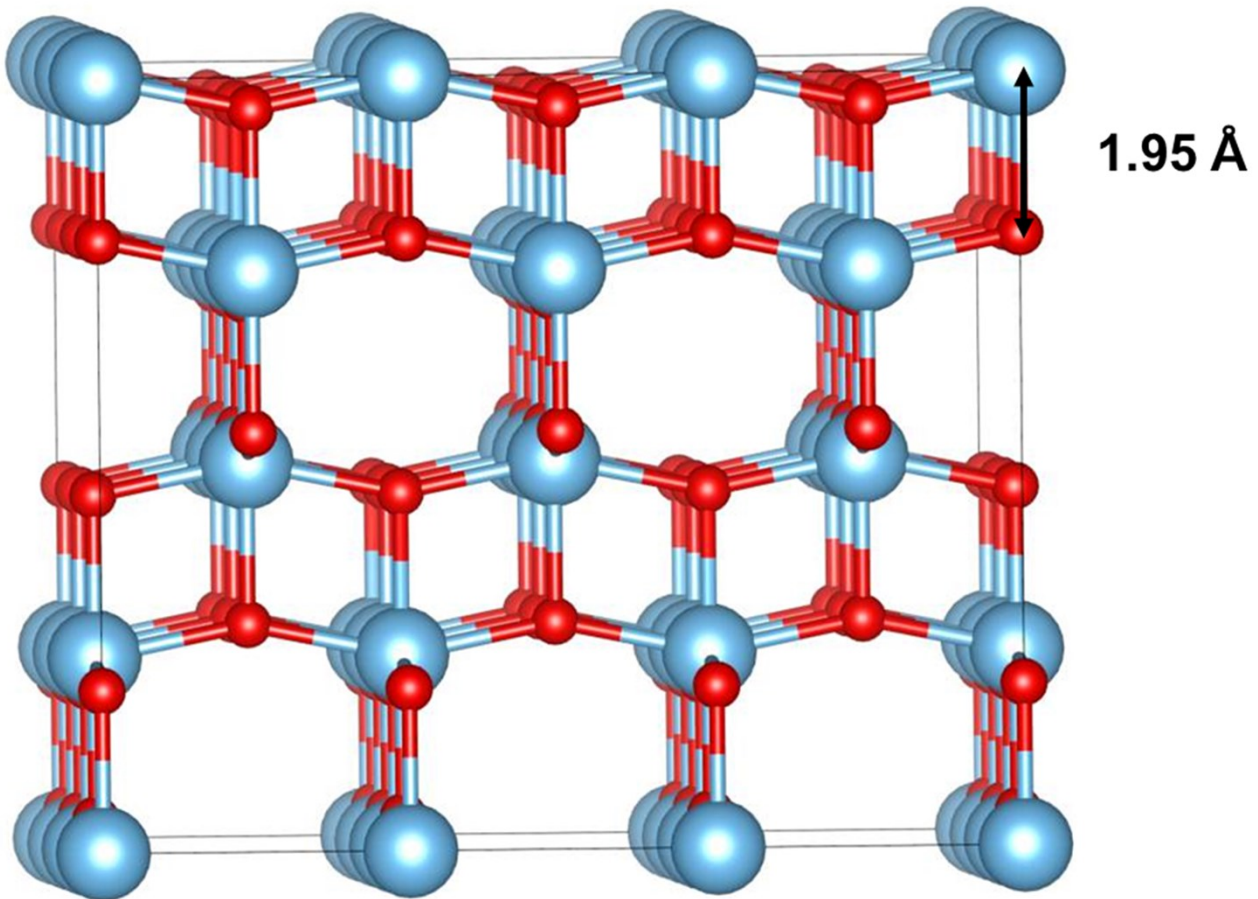
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1 Considering that Pd species were not dispersed deeply at the low additional electric field, it
2 was not detected at an early time by TOF-SIMS. Pd was belatedly detected, meaning that the Pd was
3 not well-injected into the bottom region⁵. Therefore, TOF-SIMS from the bottom to the inside is a
4 more suitable method for the purpose of analyzing the formation of heterojunction TiO₂ nanotube array
5 via the high additional electric field method. For example, TOF-SIMS can give information that the
6 Pd-doped TiO₂ nanotube array has a high Pd species region at the bottom side from when it was
7 detected. At a high additional electric field of 100 V, it can start detecting a small amount of Pd at the
8 bottom region. Therefore, the vertical *p-n* junction was formed after the application of the high
9 additional electric field of 100 V. With the high electric field, the concentration of Pd was increased
10 (Figure S3).

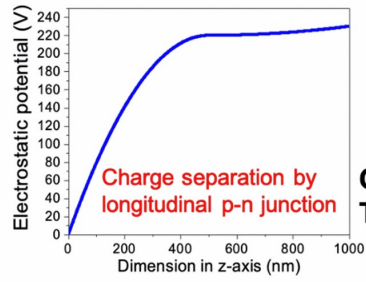
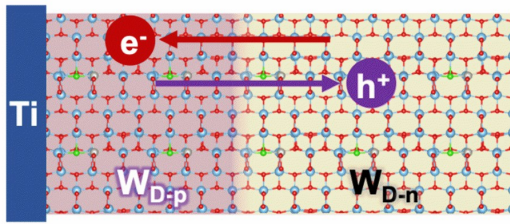


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12 **Supplementary information Figure 3.** The results of TOF-SIMS depth profile mass spectrum of the Pd-doped TiO₂
13 nanotube array with different applied high additional electric field. (a) 40 V doped, (b) 100 V doped, (c) 140 V doped,
14 and (d) comparison of the samples by fitted curves.

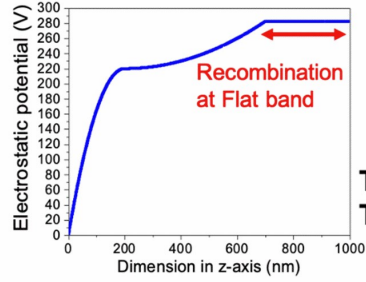
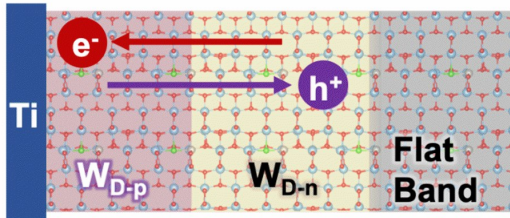
1 Using the results of the calculations, the phenomenon which occurred in the TiO₂ nanotube
2 array can be predicted with supercell model (Figure S4), as described in Figure S5. With optimum bias
3 on the Ti electrode, a vertical *p-n* junction was formed and the entire TiO₂ nanotube had band bending
4 as the charge carriers became depleted, an ideal condition for maximum photocatalytic activity (*top*
5 *panel*). When the bias was small, there was a flat band area at the top of the TiO₂ (*middle panel*);
6 hence, the photocatalytic activity was lower than that of the optimum bias. When the bias was too
7 large, the entire or large portion of the grown TiO₂ nanotube was expected to become *p*-type (*bottom*
8 *panel*). Thus, it was not suitable for water oxidation.



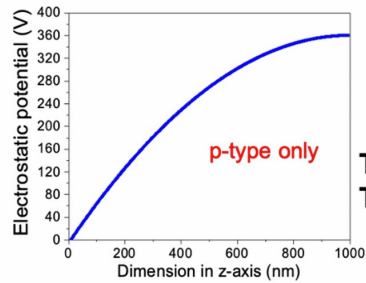
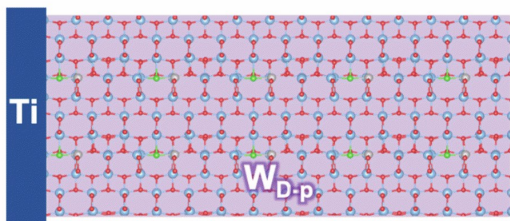
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10 **Supplementary information Figure 4.** Calculated phase space of TiO₂ and TiClO, which is expressed as the function
11 of chemical potentials of Cl and O, considering the varying atmospheric conditions during the syntheses



Optimum bias:
TNT length = $W_{D-n} + W_{D-p}$



Too small bias:
TNT length > $W_{D-n} + W_{D-p}$

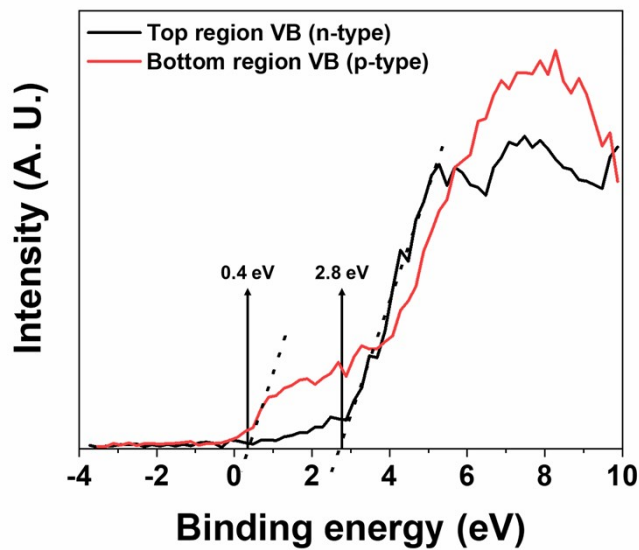


Too large bias:
TNT length < $W_{D-n} + W_{D-p}$

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Supplementary information Figure 5. Band bending with magnitudes of bias and charge densities in the TiO₂ nanotube array.

1 The valence edge of the *n*-type TiO₂ was well known as 2.6 to 2.8 eV⁶⁻⁹. Thus, the valence
2 band edge of the top region of the TiO₂ nanotube array was determined as 2.8 eV, similar to that of the
3 *n*-type TiO₂. Likewise, the valence edge of the bottom region (*p*-type region) can be predicted and
4 measured using the same method as that used in Figure S2 and S3, with the TOF-SIMS-depth profile.
5 These results showed the change in the valence band edge of the *p*- and *n*-type regions, which was 0.4
6 and 2.8 eV, respectively (Figure S6).

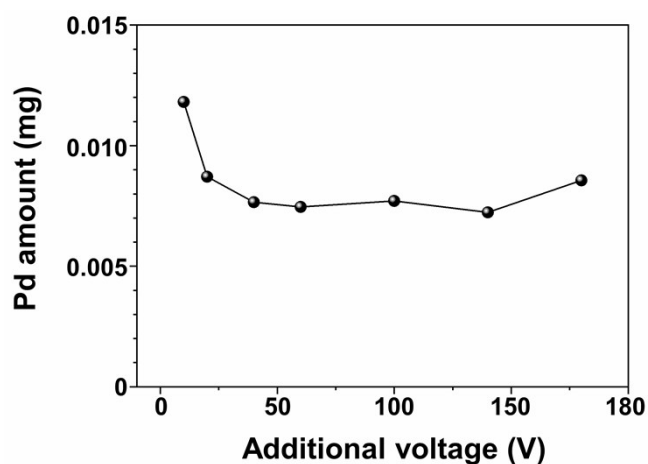


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8 **Supplementary information Figure 6.** Results of probing valence band edge at the top region (*n*-type) and bottom
9 region (*p*-type) using XPS for the detection of low binding energy.

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1 Generally, the more catalyst concentration is detected below limitation, the more catalytic
2 effect occurs; thus, it can be expected that more Pd concentration is detectable with the high additional
3 electric field. However, the saturation region and highest concentration manifested at the low
4 additional electric field, a condition of underpotential deposition⁵. Underpotential deposition was
5 reported by Kim et al. It is similar to electrophoresis because applied voltage is low and anion species
6 are attracted to the surface of the TiO₂ nanotube array. However, at a high additional electric field,
7 doped amount is decreased. The reason is that the Pd precursor, PdCl₆²⁻, is strongly aggressive, such
8 that some amount precursor is used as a dopant and the others probably etch the TiO₂ nanotube array,
9 leading to rapid breakdown anodization. Despite the separation of their roles, the doped amount of Pd
10 was limited to approximately 0.0075 mg, however, it was well-injected into the bottom region of the
11 TiO₂ nanotube array, thereby forming the vertical *p-n* junction. Therefore, despite the limiting amount
12 of Pd, the doped TiO₂ nanotube array at a high additional electric field showed higher performance
13 than that at the low additional electric field (Figure S7).

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16 **Supplementary information Figure 7.** Overall amount of Pd in TiO₂ nanotube array determined via ICP-MS.

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